

Call for papers

IC-PLANTS 2009

The 2nd International Conference on Plasma-Nanotechnology & Science

January 22-23, 2009

IB Building, Nagoya University, Nagoya JAPAN

Sponsored by Plasma Nanotechnology Research Center (PLANT), Nagoya University
Nagoya Industrial Science Research Institute

Co-sponsored by - Japan Society for Promotion of Science
- Aichi Science and Technology Foundation
(Tokai Region Knowledge Cluster Headquarters)

In conjunction with - Tokai division of the Japan Society of Applied Physics
- Tokai Branch of The Institute of Electrical Engineers of Japan
- Plasma Electronics Division, Japan Society of Applied Physics
- Plasma Center for Industrial Applications, Nagoya Urban Industrial Promotion Corporation

Plasma processing technologies are the state of the art technologies leading the way through ultra-high performance in Nano-materials, microelectronic devices, flat panels, etc. IC-PLANTS is organized for offer an opportunity for discussions and exchange of recent progress of Plasma Science and Nanotechnology among the Plasma COEs in the world. It is absolutely necessary to collaborate between the research communities for clearing the complex issues in the interdisciplinary research fields. 2nd IC-PLANTS is to be held in the Plasma Nanotechnology Research Center at Nagoya University, Japan. The Organizing Committee invites you to the conference and welcomes the submission of your papers.

General Topics

Theme: Approach to “useful” plasma science

(Plasma nanotechnologies, processes and related technologies from fundamentals to applications)

Topics: Nano-fabrication / Diagnostics and monitoring of plasmas and Reaction surfaces / Nano-electronics / Nano-biology / Interdisciplinary or integrated research with Plasma technologies / Nano-optics / NEMS technologies / Process technologies for flat panel display / Environmental technologies / Equipment technologies / Emerging new concept

Submission of Abstracts (Oral and Poster Sessions)

Abstract (A4 size, less than two pages) should be submitted by **December 1, 2008** via the web. Template is available at <http://www.plasma.engg.nagoya-u.ac.jp/IC-2009/>.

Invited Speakers

P. Awakowicz (Ruhr-Univ. Bochum, Germany), **P. Chabert** (Ecole Polytech., France), **W. Graham** (Queen's Univ. Belfast, Northern Ireland), **J. G. Han** (SungKyunKwan Univ., Korea), **T. Hayashi** (Nagoya Univ., Japan), **M. Kong** (Loughborough Univ., England), **K. K. Ostrikov** (Univ. of Sydney, Australia), **Y. Setsuhara** (Osaka Univ., Japan), **N. Umehara** (Nagoya Univ., Japan), **S. Zaima** (Nagoya Univ., Japan)

Registration Fee Early (by January 12, 2009) : General : ¥15,000.-, Student : *Free*
On-site : General : ¥20,000.-, Student : *Free*

Organizing Committee Chair

Yasuo Suzuki, Director, Plasma Nanotechnology Research Center, Nagoya University

Conatct *Hiroataka Toyoda* (Executive Committee Chair)

Makoto Sekine (Program Committee Chair)

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